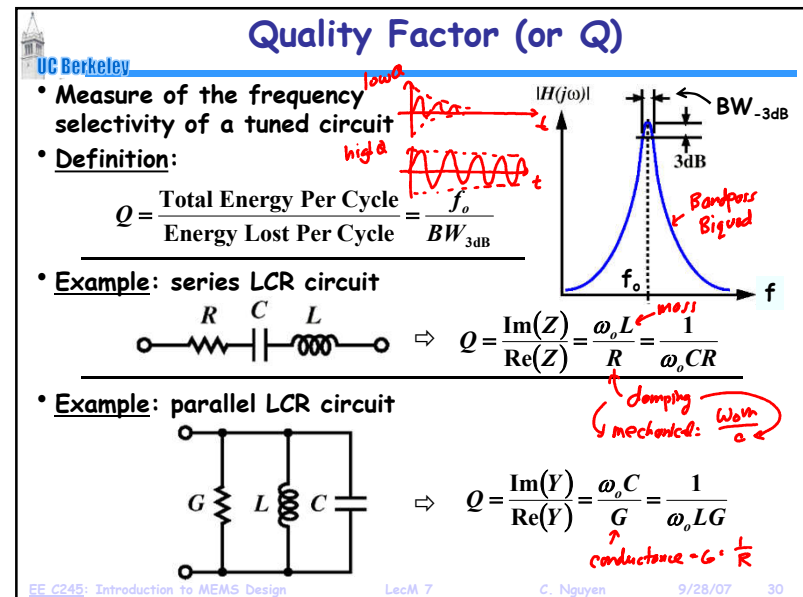
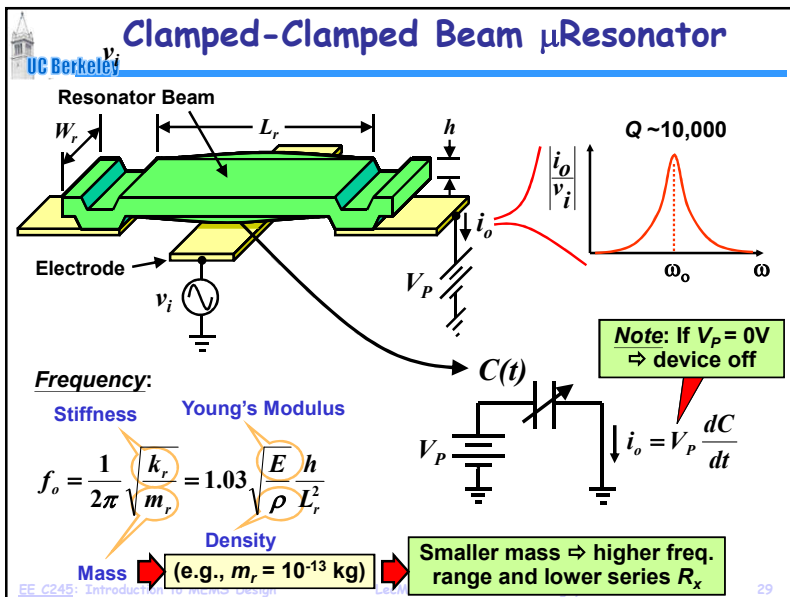


Quality Factor (or Q)

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Selective Low-Loss Filters: Need Q

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Resonator Tank Coupler Resonator Tank Coupler Resonator Tank } General BPF Implementation

Typical LC implementation:

Antenna R_x C_{x1} L_{x1} R_{x2} C_{x2} L_{x2} R_{x3} C_{x3} L_{x3} C_{12} C_{23}

Increasing Insertion Loss

Tank Q

30,000
20,000
10,000
5,000
4,000

Transmission [dB]

Frequency [MHz]

- In resonator-based filters: high tank Q \Leftrightarrow low insertion loss
- At right: a 0.1% bandwidth, 3-res filter @ 1 GHz (simulated)
 - heavy insertion loss for resonator Q < 10,000

Today: FBAR's: need Q ~ 1,000 \rightarrow BW ~ 3%

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Oscillator: Need for High Q

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- Main Function: provide a stable output frequency
- Difficulty: superposed noise degrades frequency stability

Sustaining Amplifier

Ideal Sinusoid: $v_o(t) = V_o \sin(2\pi f_o t)$

Frequency-Selective Tank

Real Sinusoid: $v_o(t) = (V_o + \epsilon(t)) \sin(2\pi f_o t + \theta(t))$

Higher Q

Tighter Spectrum

Zero-Crossing Point

$\omega_o = 2\pi/T_o$

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Attaining High Q

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- Problem: IC's cannot achieve Q's in the thousands
 - transistors \Rightarrow consume too much power to get Q
 - on-chip spiral inductors \Rightarrow Q's no higher than ~10
 - off-chip inductors \Rightarrow Q's in the range of 100's
- Observation: vibrating mechanical resonances \Rightarrow Q > 1,000
- Example: quartz crystal resonators (e.g., in wristwatches)
 - extremely high Q's ~ 10,000 or higher (Q ~ 10⁶ possible)
 - mechanically vibrates at a distinct frequency in a thickness-shear mode

Electrodes

Quartz

Thickness-Shear Mode

L_x C_x R_x C_o

$Q > 10,000$

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Energy Dissipation and Resonator Q

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Material Defect Losses

Gas Damping

$$\frac{1}{Q} = \frac{1}{Q_{\text{defects}}} + \frac{1}{Q_{\text{TED}}} + \frac{1}{Q_{\text{viscous}}} + \frac{1}{Q_{\text{support}}}$$

Thermoelastic Damping (TED)

Anchor Losses

At high frequency, this is our big problem!

Bending CC-Beam

Tension \Rightarrow Cold Spot

Heat Flux (TED Loss)

Compression \Rightarrow Hot Spot

Elastic Wave Radiation (Anchor Loss)

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Thermoelastic Damping (TED)

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- Occurs when heat moves from compressed parts to tensioned parts → heat flux = energy loss

$$\zeta = \Gamma(T)\Omega(f) = \frac{1}{2Q}$$

$$\Gamma(T) = \frac{\alpha^2 TE}{4\rho C_p}$$

$$\Omega(f_o) = 2 \left[\frac{f_{TED} f}{f_{TED}^2 + f^2} \right]$$

$$f_{TED} = \frac{\pi K}{2\rho C_p h^2}$$

ζ = thermoelastic damping factor
 α = thermal expansion coefficient
 T = beam temperature
 E = elastic modulus
 ρ = material density
 C_p = heat capacity at const. pressure
 K = thermal conductivity
 f = beam frequency
 h = beam thickness
 f_{TED} = characteristic TED frequency

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TED Characteristic Frequency

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$$f_{TED} = \frac{\pi K}{2\rho C_p h^2}$$

ρ = material density
 C_p = heat capacity at const. pressure
 K = thermal conductivity
 h = beam thickness
 f_{TED} = characteristic TED frequency

- Governed by
 - Resonator dimensions
 - Material properties

Peak where Q is minimized

Property	Silicon	Quartz	Units
Thermal expansion	2.60	13.70	ppm/°K
Elastic modulus	1.70	0.78	10 ¹² dyne/cm ²
Material density	2.33	2.60	g/cm ³
Heat capacity	0.70	0.75	J/g/°K
Thermal conductivity	1.50	0.10	10 ⁷ dyne/°K/s
Peak damping @ 300°K	1.06	11.34	10 ⁻⁴

[from Roszhart, Hilton Head 1990]

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Q vs. Temperature

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Quartz Crystal

Q ~5,000,000 at 30K

Q ~300,000,000 at 4K

Mechanism for Q increase with decreasing temperature thought to be linked to less hysteretic motion of material defects → less energy loss per cycle

Aluminum Vibrating Resonator

Q ~500,000 at 30K

Q ~1,250,000 at 4K

Even aluminum achieves exceptional Q's at cryogenic temperatures

[from Braginsky, Systems With Small Dissipation]

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Polysilicon Wine-Glass Disk Resonator

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Compound Mode (2,1)

Input Output

Wine Glass Disk Resonator

Anchor

Support Beams

Input Output

$R = 32 \mu\text{m}$

Unmatched Transmission [dB]

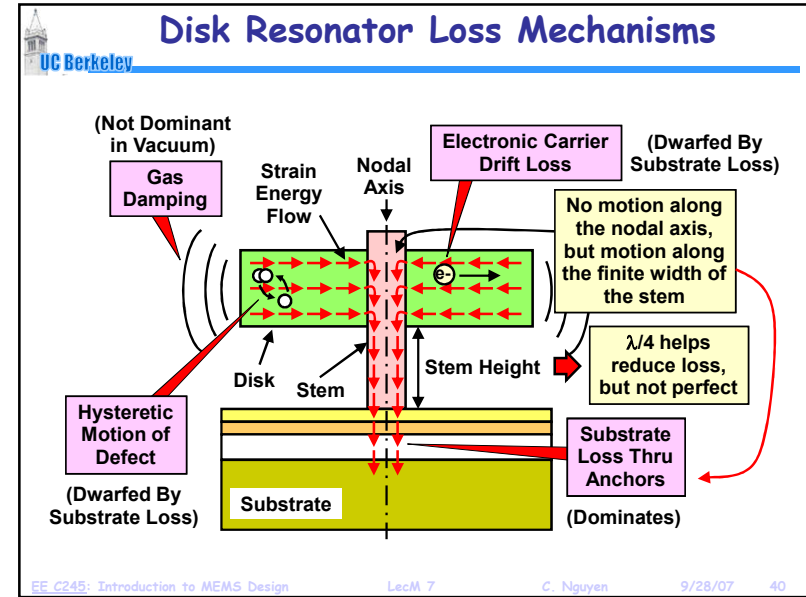
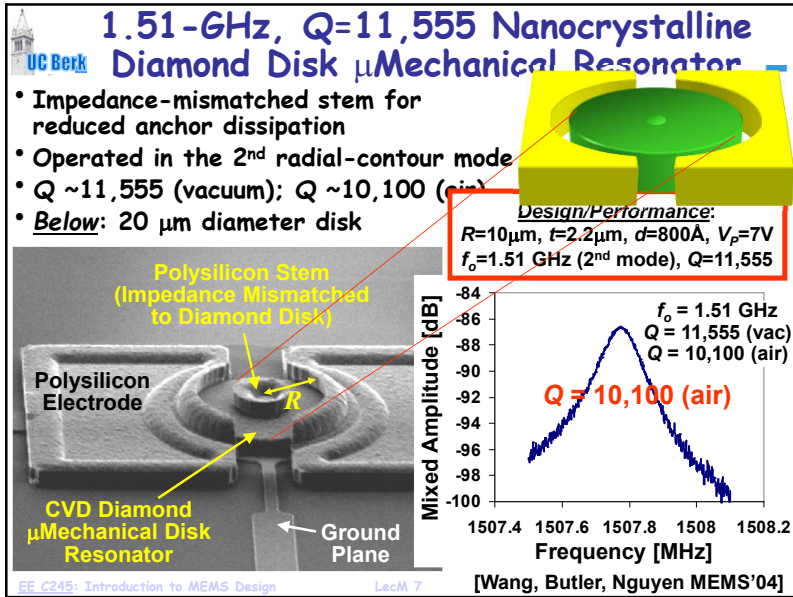
$f_o = 61.37 \text{ MHz}$
 $Q = 145,780$

Frequency [MHz]

Resonator Data
 $R = 32 \mu\text{m}$, $h = 3 \mu\text{m}$
 $d = 80 \text{ nm}$, $V_p = 3 \text{ V}$

[Y.-W. Lin, Nguyen, JSSC Dec. 04]

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MEMS Material Property Test Structures

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Stress Measurement Via Wafer Curvature

- Compressively stressed film \rightarrow bends a wafer into a convex shape
- Tensile stressed film \rightarrow bends a wafer into a concave shape
- Can optically measure the deflection of the wafer before and after the film is deposited
- Determine the radius of curvature R , then apply:

$$\sigma = \frac{E'h^2}{6Rt}$$

σ = film stress [Pa]
 $E' = E/(1-\nu)$ = biaxial elastic modulus [Pa]
 h = substrate thickness [m]
 t = film thickness
 R = substrate radius of curvature [m]

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MEMS Stress Test Structure

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- Simple Approach:** use a clamped-clamped beam
- Compressive stress causes buckling
- Arrays with increasing length are used to determine the critical buckling load, where

$$\sigma_{critical} = -\frac{\pi^2 E h^2}{3 L^2}$$

E = Young's modulus [Pa]
I = (1/12)Wh³ = moment of inertia
L, W, h indicated in the figure

Limitation: Only compressive stress is measurable

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More Effective Stress Diagnostic

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- Single structure measures both compressive and tensile stress
- Expansion or contraction of test beam → deflection of pointer
- Vernier movement indicates type and magnitude of stress

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Q Measurement Using Resonators

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Compound Mode (2,1)

Wine Glass Disk Resonator
R = 32 μm

Resonator Data
R = 32 μm, h = 3 μm
d = 80 nm, V_p = 3 V

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Folded-Beam Comb-Drive Resonator

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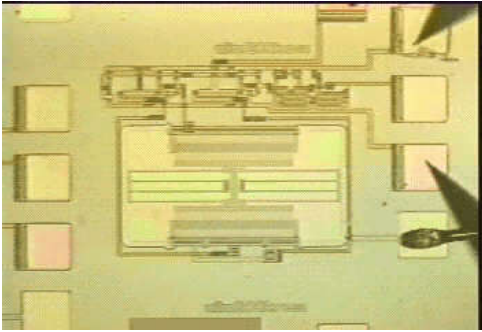
- Issue w/ Wine-Glass Resonator:** non-standard fab process
- Solution:** use a folded-beam comb-drive resonator

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Comb-Drive Resonator in Action

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- Below: fully integrated micromechanical resonator oscillator using a MEMS-last integration approach

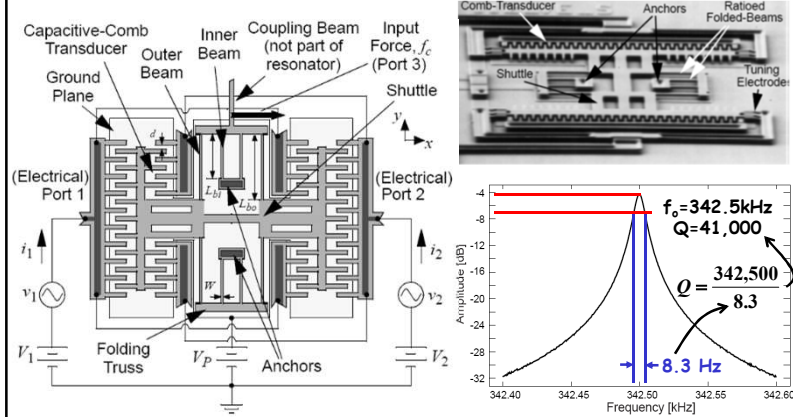


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Folded-Beam Comb-Drive Resonator

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- Issue w/ Wine-Glass Resonator: non-standard fab process
- Solution: use a folded-beam comb-drive resonator



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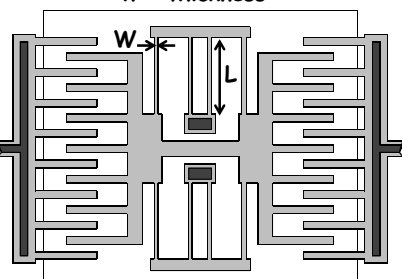
Measurement of Young's Modulus

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- Use micromechanical resonators
- Resonance frequency depends on E
- For a folded-beam resonator:

$$\text{Resonance Frequency} = f_o = \left[\frac{4Eh(W/L)^3}{M_{eq}} \right]^{1/2}$$

h = thickness



Young's modulus

Equivalent mass

- Extract E from measured frequency f_o
- Measure f_o for several resonators with varying dimensions
- Use multiple data points to remove uncertainty in some parameters

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Anisotropic Materials

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Elastic Constants in Crystalline Materials

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- Get different elastic constants in different crystallographic directions → 81 of them in all
 - Cubic symmetries make 60 of these terms zero, leaving 21 of them remaining that need be accounted for
- Thus, describe stress-strain relations using a 6x6 matrix

$$\begin{bmatrix} \sigma_x \\ \sigma_y \\ \sigma_z \\ \tau_{yz} \\ \tau_{zx} \\ \tau_{xy} \end{bmatrix} = \begin{bmatrix} C_{11} & C_{12} & C_{13} & C_{14} & C_{15} & C_{16} \\ C_{12} & C_{22} & C_{23} & C_{24} & C_{25} & C_{26} \\ C_{13} & C_{23} & C_{33} & C_{34} & C_{35} & C_{36} \\ C_{14} & C_{24} & C_{34} & C_{44} & C_{45} & C_{46} \\ C_{15} & C_{25} & C_{35} & C_{45} & C_{55} & C_{56} \\ C_{16} & C_{26} & C_{36} & C_{46} & C_{56} & C_{66} \end{bmatrix} \begin{bmatrix} \epsilon_x \\ \epsilon_y \\ \epsilon_z \\ \gamma_{yz} \\ \gamma_{zx} \\ \gamma_{xy} \end{bmatrix}$$

↑ Stresses Stiffness Coefficients ↑ Strains

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Stiffness Coefficients of Silicon

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- Due to symmetry, only a few of the 21 coefficients are non-zero
- With cubic symmetry, silicon has only 3 independent components, and its stiffness matrix can be written as:

$$\begin{bmatrix} \sigma_x \\ \sigma_y \\ \sigma_z \\ \tau_{yz} \\ \tau_{zx} \\ \tau_{xy} \end{bmatrix} = \begin{bmatrix} C_{11} & C_{12} & C_{13} & 0 & 0 & 0 \\ C_{12} & C_{22} & C_{23} & 0 & 0 & 0 \\ C_{13} & C_{23} & C_{33} & 0 & 0 & 0 \\ 0 & 0 & 0 & C_{44} & 0 & 0 \\ 0 & 0 & 0 & 0 & C_{55} & 0 \\ 0 & 0 & 0 & 0 & 0 & C_{66} \end{bmatrix} \begin{bmatrix} \epsilon_x \\ \epsilon_y \\ \epsilon_z \\ \gamma_{yz} \\ \gamma_{zx} \\ \gamma_{xy} \end{bmatrix}$$

where $\begin{cases} C_{11} = 165.7 \text{ GPa} \\ C_{12} = 63.9 \text{ GPa} \\ C_{44} = 79.6 \text{ GPa} \end{cases}$

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